

# Gregory Blachut

## List of Publications by Year in descending order

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Version: 2024-02-01

22  
papers

1,070  
citations

687363

13  
h-index

713466

21  
g-index

22  
all docs

22  
docs citations

22  
times ranked

974  
citing authors

#	ARTICLE	IF	CITATIONS
1	Spatial Control of the Self-assembled Block Copolymer Domain Orientation and Alignment on Photopatterned Surfaces. ACS Applied Materials & Interfaces, 2020, 12, 23399-23409.	8.0	7
2	Characterizing the Interface Scaling of High $\chi$ Block Copolymers near the Order-Disorder Transition. Macromolecules, 2018, 51, 173-180.	4.8	34
3	Evolution of roughness during the pattern transfer of high- $\chi$ , 10nm half-pitch, silicon-containing block copolymer structures. , 2018, , .		3
4	Generating Large Thermally Stable Marangoni-Driven Topography in Polymer Films by Stabilizing the Surface Energy Gradient. Macromolecules, 2017, 50, 4588-4596.	4.8	18
5	Influence of topographically patterned angled guidelines on directed self-assembly of block copolymers. Physical Review E, 2017, 96, 052501.	2.1	3
6	Directed Self-Assembly and Pattern Transfer of Five Nanometer Block Copolymer Lamellae. ACS Nano, 2017, 11, 7656-7665.	14.6	103
7	High- $\chi$ , Si-Containing Block Copolymers and Process Strategies for Directing Their Self-Assembly. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 187-190.	0.3	2
8	Plasma and photon interactions with organosilicon polymers for directed self-assembly patterning applications. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2016, 34, .	1.2	7
9	A Hybrid Chemo-/Grapho-Epitaxial Alignment Strategy for Defect Reduction in Sub-10 nm Directed Self-Assembly of Silicon-Containing Block Copolymers. Chemistry of Materials, 2016, 28, 8951-8961.	6.7	28
10	Synthesis and Characterization of Si-containing Block Co-polymers with Resolution beyond 10 nm. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 701-704.	0.3	4
11	Pattern Transfer of Sub-10 nm Features via Tin-Containing Block Copolymers. ACS Macro Letters, 2016, 5, 391-395.	4.8	22
12	Interactions between plasma and block copolymers used in directed self-assembly patterning. Proceedings of SPIE, 2016, , .	0.8	8
13	Structure, Stability, and Reorganization of 0.5 $\mu\text{m}$ Topography in Block Copolymer Thin Films. ACS Nano, 2016, 10, 10152-10160.	14.6	38
14	Experimental and Modeling Study of Domain Orientation in Confined Block Copolymer Thin Films. Macromolecules, 2016, 49, 308-316.	4.8	34
15	Interfacial Layers with Photoswitching Surface Energy for Block Copolymer Alignment and Directed Self-Assembly. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2015, 28, 611-615.	0.3	4
16	Double-Patterned Sidewall Directed Self-Assembly and Pattern Transfer of Sub-10 nm PTMSS- $\text{b}$ -PMOST. ACS Applied Materials & Interfaces, 2015, 7, 13476-13483.	8.0	60
17	Directed Self-Assembly of Silicon-Containing Block Copolymer Thin Films. ACS Applied Materials & Interfaces, 2015, 7, 3323-3328.	8.0	68
18	Design of high- $\chi$ block copolymers for lithography. Journal of Polymer Science Part A, 2015, 53, 344-352.	2.3	136

#	ARTICLE	IF	CITATIONS
19	Interfacial Design for Block Copolymer Thin Films. Chemistry of Materials, 2014, 26, 1471-1479.	6.7	108
20	Photopatternable Interfaces for Block Copolymer Lithography. ACS Macro Letters, 2014, 3, 824-828.	4.8	28
21	Block Copolymers for DSA in the 100 nm Regime. Journal of Photopolymer Science and Technology = [Fotopolyma Konwakai Shi], 2014, 27, 415-418.	0.3	1
22	Polarity-Switching Top Coats Enable Orientation of Sub-10-nm Block Copolymer Domains. Science, 2012, 338, 775-779.	12.6	354